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**INFORMATION DISCLOSURE STATEMENT  
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Applicant: JOHNSON et al.

Appln. No.: 10/076,099

Filing Date: February 15, 2002

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Page 1 of 4

Examiner: Not Assigned

Group Art Unit: 1762

**U.S. PATENT DOCUMENTS**

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
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	BR	4,993,358	02/1991	MAHAWILI	118	715	
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10/31/05

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
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	PR					
	QR					

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

<i>Jm</i>	RR	Bird, Molecular Gas Dynamics and the Direct Simulation of Gas Flows, Claredon Press, 1994, pp. 2-3.			
	SR	Gentry et al., "Ten-microsecond pulsed molecular beam source and a fast ionization detector," Rev. Sci. Instru, 49(5), May 1978, pp. 595-600.			
	TR	Samukawa et al., "Pulse-time modulated electron cyclotron resonance plasma etching for highly selective, highly anisotropic, and less-charging polycrystalline silicon patterning," J. Vac. Sci. Technol. B 12(6), Nov/Dec 1994, pp. 3300-3305.			
	UR	Sugai et al., "Diagnostics and control of high-density etching plasmas," Mat. Res. Soc. Symp., Proc. Vol 406, 1996, pp. 15-25.			
	VR	Yeon et al., "Study of particulate formation and its control by a radio frequency power modulation in the reactive ion process of SiO2 with CF4H2 Plasma" J. Vac. Sci. Technol. A 15(1), Jan/Feb 1997, pp. 66-71.			
<i>Jm</i>	WR	Bates, et al., "Fast gas injection system for plasma physics experiments," Rev. Sci. Instrum. 55(6) June 1984, pp. 934-939.			

Examiner *Bohney*

Date Considered: 9/4/03

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.